Title: Wetting Behaviour of Carbon Nitride Nanostructures Grown by Plasma Enhanced Chemical Vapour Deposition Technique

Author: Shafarina Azlinda Ahmad Kamal Richard Ritikos Saadah Abdul Rahman

PII: S0169-4332(14)02688-9
DOI: http://dx.doi.org/doi:10.1016/j.apsusc.2014.12.001
Reference: APSUSC 29235

To appear in: *APSUSC*

Received date: 4-8-2014
Revised date: 1-12-2014
Accepted date: 1-12-2014

Please cite this article as: S.A.A. Kamal, R. Ritikos, S.A. Rahman, Wetting Behaviour of Carbon Nitride Nanostructures Grown by Plasma Enhanced Chemical Vapour Deposition Technique, *Applied Surface Science* (2014), http://dx.doi.org/10.1016/j.apsusc.2014.12.001

WETTING BEHAVIOUR OF CARBON NITRIDE NANOSTRUCTURES GROWN BY PLASMA ENHANCED CHEMICAL VAPOUR DEPOSITION TECHNIQUE

Shafarina Azlinda Ahmad Kamal, Richard Ritikos and Saadah Abdul Rahman*

Low Dimensional Materials Research Centre, Department of Physics, University of Malaya,

50603 Kuala Lumpur, Malaysia

*Corresponding author**:** Email: shafarinaazlinda@yahoo.com